

Unconventionell lithographies

Nanolithography is well established in computer industry, lateral dimensions below 30nm are achieved nowadays. Nevertheless the methods used there consist of expensive apparatus. Alternative approaches for nanostructuring should be inexpensive, fast and flexible. Two approaches which fulfill these requirements will be discussed: colloidal monolayer lithography and pulsed laser interference lithography. In the first the triangular holes which appear between three particles in an ordered particle monolayer are used as a mask, while in the second method the laser interference pattern is used directly for surface modification.